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APPLICATION NO.	FILING DATE	FIRST NAMED IN	VENTOR		ATTORNEY DOCKET NO.
09/436,092	11/08/99	ANDIDEH		E	043290.P3955
_		- N 100	$\neg$		EXAMINER
QM32/0828 DARREN J MILLIKEN				MCDON	ALD,S
- · · · · · · · · · · · · · · · · · · ·		R & ZAFMAN LLP		ART UNIT	FAPER NUMBER
12400 WILSHI SEVENTH FLOO LOS ANGELES	)R			3723 DATE MAILE	<b>)</b> 08/28/01

Please find below and/or attached an Office communication concerning this application or proceeding.

**Commissioner of Patents and Trademarks** 



## Office Action Summary

Application No. 09/436,092

Applicant(s)

Examiner

Art Unit

Shantese McDonald

3723

Andideh et al.

	The MAILING DATE of this communication appears of	on the cover sheet with the correspondence address			
	or Reply				
THEN	DRTENED STATUTORY PERIOD FOR REPLY IS SET MAILING DATE OF THIS COMMUNICATION.				
aft	er SIX (6) MONTHS from the mailing date of this communication	R 1.136 (a). In no event, however, may a reply be timely filed			
- If the	period for reply specified above is less than thirty (30) days, considered timely.	a reply within the statutory minimum of thirty (30) days will			
- If NO	period for reply is specified above, the maximum statutory p	eriod will apply and will expire SIX (6) MONTHS from the mailing date of this			
- Failur	mmunication. e to reply within the set or extended period for reply will, by	statute, cause the application to become ABANDONED (35 U.S.C. § 133).			
- Any r ea	eply received by the Office later than three months after the med patent term adjustment. See 37 CFR 1.704(b).	mailing date of this communication, even if timely filed, may reduce any			
Status	•				
1) 💢	Responsive to communication(s) filed on a CPA file	d August 6, 2001			
•					
3) 🗆	Since this application is in condition for allowance e closed in accordance with the practice under Ex pair	except for formal matters, prosecution as to the merits is rete Quayle, 1935 C.D. 11; 453 O.G. 213.			
Disposi	tion of Claims				
4) 💢	Claim(s) <u>54-75</u>	is/are pending in the application.			
4	a) Of the above, claim(s)	is/are withdrawn from consideration.			
5) 🗆	Claim(s)	is/are allowed.			
6) 💢	Claim(s) <u>54-75</u>	is/are rejected.			
7) 🗆	Claim(s) is/are objected to.				
8) 🗆	Claims	are subject to restriction and/or election requirement.			
Applica	tion Papers				
9) 🗆	The specification is objected to by the Examiner.				
10)□	The drawing(s) filed on is/are				
11)□	The proposed drawing correction filed on	is: a) $\square$ approved b) $\square$ disapproved.			
12)	The oath or declaration is objected to by the Exami	iner.			
	under 35 U.S.C. § 119				
13) Acknowledgement is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d).					
a) [	☐ All b)☐ Some* c)☐ None of:				
	1. Certified copies of the priority documents have				
	2. Certified copies of the priority documents have				
	<ol> <li>Copies of the certified copies of the priority d application from the International Bure ee the attached detailed Office action for a list of th</li> </ol>	ocuments have been received in this National Stage au (PCT Rule 17.2(a)). e certified copies not received.			
	Acknowledgement is made of a claim for domestic				
Attachment(s)					
	lotice of References Cited (PTO-892)  lotice of Draftsperson's Patent Drawing Review (PTO-948)	18) Interview Summary (PTO-413) Paper No(s).  19) Notice of Informal Patent Application (PTO-152)			
17) Information Disclosure Statement(s) (PTO-1449) Paper No(s)					
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#### **DETAILED ACTION**

1. The drawings are objected to under 37 CFR 1.83(a). The drawings must show every feature of the invention specified in the claims. Therefore, the wafer, device for determining topography, device for determining high and low points and the slurry must be shown or the feature(s) canceled from the claim(s). No new matter should be entered.

## Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless --

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 3. Claims 54-72 and 75 are rejected under 35 U.S.C. 102(b) as being anticipated by Burke et al.

Burke et al teaches a polishing pad 130, having a center area (fig 8), and an edge area, with a first set of grooves located in the center area with a first depth, first width, and first density, a second set of grooves located in the edge area with a second set of grooves having a second depth, second width and a second density. Burke et al. also teaches that the first depth, width and density is smaller than the second depth, width and density, and that the first set of grooves and the second set of grooves differ in shape.

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### Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claims 73 and 74 are rejected under 35 U.S.C. 103(a) as being unpatentable over Burke et al. in view of Sandhu et al.

Burke et al. teaches all the limitations of the claims except for a device for determining profile or topography of a wafer, and a device for determining high and low points of the wafer. Sandhu et al. teaches a device, 60 for measuring topography and high and low points. It would have been obvious to one having ordinary skill in the art at the time the invention was made, to provide the apparatus of Burke et al with a measuring device, as taught by Sandhu et al., in order to enhance the processing of the wafer.

#### Conclusion

6. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. James et al. and Morgan, III et al. were cited to show other examples of polishing pads.

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7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Shantese McDonald whose telephone number is (703) 308-8722.

Joseph J. Hail, III Supervisory Patent Examiner Technology Center 3700

Just q. Haile

S.L.M.

August 24, 2001